



## APPENDIX A

Helbert et al., SPIE Vol. 333 Submicron Lithography (1982): this publication generally relates to, *inter alia*, hybrid ultragraphic process using both electron beam and conventional optical exposure within the same device level with a photoresist.

\*Kozicki et al., Superlattices and Microstructures, 27 (2000): this publication generally relates to, *inter alia*, solid solutions of metals (e.g., silver) in arsenic trisulfide and their physical and electrical characteristics.

\*Kozicki et al., Microelectronic Engineering, vol. 63/1-3 (2002): this publication generally relates to, *inter alia*, the photodiffusion of Ag into germanium selenide glass films, the amount of Ag that can be incorporated in to such a film by photodiffusion, and the characteristics of the resulting doped films.

\*Kozicki et al., Proceedings of the 1999 Symposium on Solid State Ionic Devices (1999): this publication generally relates to, *inter alia*, physical and electrical characteristics of metal doped chalcogenide films (photodoped  $\text{Ag}_4\text{As}_2\text{S}_3$ ) between electrodes, useful in memories, configurable connections, and self-repairing interconnections.

\*Kozicki and Mitkova, Proceedings of the XIX International Congress on Glass, Society for Glass Technology (2001): this publication generally relates to, *inter alia*, the physical effects of introduction of Ag into chalcogenide glasses, where introduction is by photodiffusion.

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